

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of:

TAKESHI OHFUJI, ET AL.

Application No.: 09/965,280

Filed: September 26, 2001



Art Group: 1756

Examiner: Mohamedulla, S.

For: **POST EXPOSURE MODIFICATION OF
CRITICAL DIMENSIONS IN MASK
FABRICATION**

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

In accordance with the duty of disclosure, enclosed is a copy of IDS Citation Form PTO/SB/08 or PTO-1449.

This IDS and IDS Citation Form are being submitted before the mailing of a final Office Action. It is respectfully requested that the cited references be considered and that the enclosed copy of PTO/SB/08 be initialed by the Examiner to indicate such consideration and a copy thereof returned to applicant(s).

The submission of this Information Disclosure Statement is not to be construed as a representation that a search has been made in the subject application and is not to be construed as an admission that the information cited in this statement is material to patentability.

Date: Nov. 24, 2004

Respectfully submitted,

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I hereby certify that this correspondence is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Krista Mathieson Nov. 24, 2004
Krista Mathieson Date



US Department of Commerce Patent and Trademark Office Form PTO-1449 (Modified)	Atty. Docket No.: 42390P11370	Application No.: 09/965,280
	Applicant: Ohfiji et al.	
	Filing Date: September 26, 2001	

US Patent Documents

Examiner's Initials		Date	Document Number	Name	Class	Sub-Class	Filing Date

Foreign Patent Documents

Examiner's Initials		Date	Document Number	Country	Class	Sub-Class	Translation

Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)

	Alexei L. Bogdanov, Use of SU-8 Negative Photoresist for Optical Mask Manufacturing MAX-Lab, University of Lund, SE-221 00, Lund Sweden. [online] Pages 1-11. http://www.maxlab.luy.se/beamlines/bld811 . Proc. SPIE Vol. 3999. Pub. 2000.
	SPIE Volume 2512; Masumi Arai, Hiroyuki Inomata, Toshiharu Nishimura, Masa-aki Kurihara and Naoya Hayashi; "Application of Chemically Amplified Resists to Photomask Fabrication". Micro Products Research Laboratory, Micro Products Division, Dai Nippon Printing CO., Ltd., Japan. Pages 74-87. Pub. 1995.
	SPIE Volume 2793; A Chemically Amplified Resist Process For 0.25 μ M Generation Photomasks; Mikio Katsumata, Hiroichi Kawahira, Minoru Sugara and Satoru Nozawa. MOS LSI Division, Semiconductor Company, Sony Corporation, Japan. Pages 96-104. Pub. 1996.

Examiner	Date Considered

Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw a line through the citation if not in conformance and not considered. Include a copy of this form with the next communication to the applicant

* Did not receive any NPLs.